## What is claimed is:

1	1. A method for sampling a high temperature process stream, comprising
2	the steps of:
3	evacuating a low temperature zone of a sampling system using a vacuum pump;
4	admitting a portion of the high temperature process stream into the low
5	temperature zone through an orifice;
6	maintaining a stable vacuum pressure in the low temperature zone; and
7 -	introducing a sample from the low temperature zone of the sampling system into
8.	test equipment through a sample introduction valve.
1	2. The method of claim 1, wherein the orifice has a diameter of between
2 .	0.005 inches and 0.025 inches.
ĺ	3. The method of claim 1, wherein the step of maintaining a stable
2	vacuum pressure in the low temperature zone includes metering flow to the vacuum
3	pump.
1	4. The method of claim 1, wherein the step of maintaining a stable
2	vacuum pressure in the low temperature zone includes controlling the vacuum pump.
1	5. The method of claim 1, wherein a temperature of the high temperature
2	process stream is above a boiling point of a target sample component at the process
3 .	stream pressure.

6. The method of claim 1, further comprising the step of maintaining a temperature of the low temperature zone above a boiling point of a target sample 5 component at the stable vacuum pressure. 6 7. The method of claim 1, wherein the test equipment includes a mass spectrometer. 2 The method of claim 1, wherein the test equipment includes a FT-ICR mass spectrometer. 2 9. The method of claim 8, wherein the FT-ICR mass spectrometer 2. includes a second vacuum pump, and the method further comprises the step of evacuating with the second vacuum pump a chamber of the FT-ICR to a pressure lower than the 4 stable vacuum pressure in the low temperature zone. The method of claim 1, wherein the stable vacuum pressure is between a pressure of the process stream and a high vacuum pressure of a vacuum chamber of the test equipment. 3 A sampling system for sampling a high temperature process stream to 2 be tested in an analytical instrument, the sampling system comprising: an evacuation system for maintaining a low temperature zone of the sampling 3 system at a vacuum pressure; 4 5 a nozzle having an orifice connecting the sample stream with the low pressure

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zone of the sampling system; and

- a sample introduction valve connecting the low temperature zone of the sampling system with a vacuum chamber of the analytical instrument, the sample introduction valve being located between the evacuation system and the nozzle.
- 1 12. The sampling system of claim 11, wherein the analytical instrument is 2 a mass spectrometer.
- 1 13. The sampling system of claim 11, wherein the analytical instrument is 2 an FT-ICR mass spectrometer.
- 1 14. The sampling system of claim 11, wherein the evacuation system 2 comprises a vacuum pump.
- 1 15. The sampling system of claim 14, wherein the evacuation system
  2 further comprises a metering valve for metering an intake of the vacuum pump.
- 1 16. The sampling system of claim 11, wherein the orifice has a diameter of between 0.005 inches and 0.025 inches.
- 1 17. A method for sampling from a gaseous process stream at a process
  2 stream temperature and pressure, the stream having at least one component with a first
  3 boiling point lower than the process stream temperature when at the process stream
  4 pressure, the method comprising the steps of:
- admitting a gas sample from the process stream through an orifice into a sampling system, the sampling system having a sampling system temperature lower than the first boiling point, the sampling system further having a sampling system pressure lower than

- the process stream pressure, whereby the component in the gas sample has a second
- 9 boiling point at the sampling system pressure, the second boiling point being lower than
- the sampling system temperature; and
- introducing a portion of the gas sample into a test instrument chamber.
- 1 18. The method of claim 17, wherein the step of introducing the portion of
- 2 the gas sample into the test instrument chamber includes pulsing a piezoelectric valve.
- 1 19. The method of claim 17, wherein the orifice is between 0.005 inches
- and 0.025 inches in diameter.
- 1 20. The method of claim 17, further comprising the step of maintaining a
- 2 stable vacuum pressure in the sampling system.
- 1 21. The method of claim 20, wherein the step of maintaining a stable
- 2 vacuum pressure in the sampling system includes regulating a vacuum pump throughput.
- 1 22. The method of claim 20, wherein the step of maintaining a stable
- 2 vacuum pressure in the sampling system includes regulating a valve that meters flow
- 3 through a vacuum pump.